

Due: Monday, March 10, 2003

1. An abrupt Si p-n junction is formed by alloying a uniformly doped n-type silicon bar where $N_d = 8 \times 10^{16} / \text{cm}^3$ in the beginning. During the alloying process, a uniform counter doping of acceptors of $N_a = 1.4 \times 10^{17} / \text{cm}^3$ is introduced in the region for $x < 0$. Basically, $x < 0$ is the p-side and $x > 0$ is the n-side.
- Calculate the Fermi level positions at 300 K in the p and n regions.
 - Draw an equilibrium band diagram for the junction and determine the contact potential V_o from the diagram.
 - Compare the results of part (b) with V_o as calculated from Eq. (5-8).
 - Using Eq. (5-8), calculate and plot V_o versus temperature ranging from 250 K to 500 K.

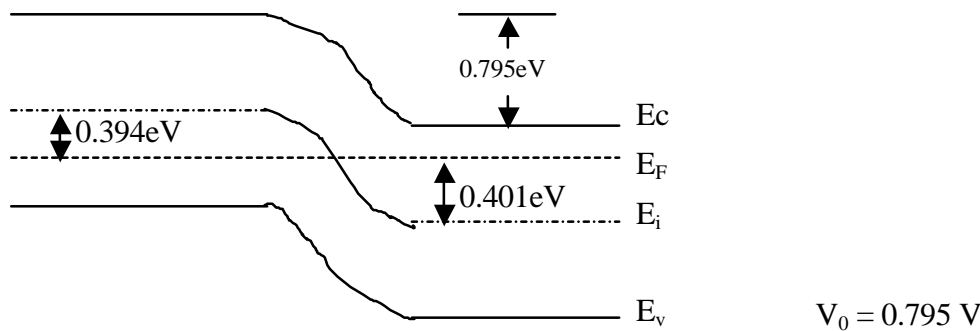
Solutions:

(a), At $x < 0$, $p_p = N_a - N_d = 6 \times 10^{16} \text{ cm}^{-3}$

$$\text{In p region, } E_{ip} - E_{Fp} = \frac{kT}{q} \ln \frac{p}{n_i} = 0.0259 \times \ln \frac{6 \times 10^{16}}{1.5 \times 10^{10}} = 0.394 \text{ eV}$$

$$\text{In n region, } E_{Fn} - E_{in} = \frac{kT}{q} \ln \frac{n}{n_i} = 0.0259 \times \ln \frac{8 \times 10^{16}}{1.5 \times 10^{10}} = 0.401 \text{ eV}$$

(b),



(c), Equations 5-8:

$$V_o = 0.0259 \ln \frac{N_a N_d}{n_i^2} = 0.0259 \ln \frac{6 \times 10^{16} \times 8 \times 10^{16}}{(1.5 \times 10^{10})^2} = 0.795 \text{ V}$$

Result is same as (b)

(d), Notice that the n_i is related to temperature through Eq. 3-26

Method 1:

Read n_i from Figure 3-17, plug into Eqn 5-8 to obtain the plot.

For example: at $T = 400 \text{ K}$, $n_i = 8 \times 10^{12} \text{ cm}^{-3}$.

$$V_o = \frac{kT}{q} \ln \frac{N_a N_d}{n_i^2} = \frac{1.38 \times 10^{-23} \times 400}{1.6 \times 10^{-19}} \ln \frac{6 \times 10^{16} \times 8 \times 10^{16}}{(8 \times 10^{12})^2} = 0.626 \text{ V}$$

At least 5 points must be correctly read and calculated.

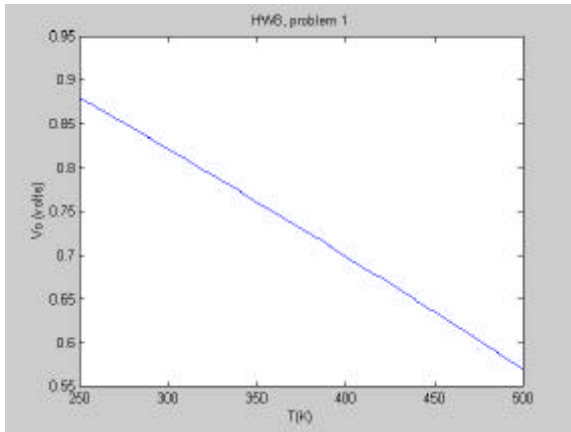
Method 2

$n_i(T) = 2 \left(\frac{2pkT}{h^2} \right)^{3/2} (m_n^* m_p^*)^{3/4} e^{-E_g/2kT}$, therefore, if we assume m_n^*, m_p^*, E_g is independent of T, we have:

$$\frac{n_i(T)}{n_i(300K)} = \left(\frac{T}{300} \right)^{3/2} e^{\left[-\frac{E_g}{2k} \left(\frac{1}{T} - \frac{1}{300} \right) \right]}, \quad \text{i.e.,} \quad n_i(T) = n_i(300K) \left(\frac{T}{300} \right)^{3/2} e^{\left[-\frac{E_g}{2k} \left(\frac{1}{T} - \frac{1}{300} \right) \right]}$$

$$\begin{aligned} V_0 &= \frac{kT}{q} \ln \frac{N_a N_d}{n_i^2} = \frac{kT}{q} \ln \frac{N_a N_d}{\left(n_i(300K) \left(\frac{T}{300} \right)^{3/2} e^{\left[-\frac{E_g}{2k} \left(\frac{1}{T} - \frac{1}{300} \right) \right]} \right)^2} \\ &= \frac{kT}{q} \left[\ln \frac{N_a N_d}{n_i^2(300K)} - 3(\ln T - \ln 300) + \frac{E_g}{k} \left(\frac{1}{T} - \frac{1}{300} \right) \right] \\ &= \frac{1.38 \times 10^{-23} \times T}{1.6 \times 10^{-19}} \left[30.69 - 3 \ln T + 3 \ln 300 + \frac{1.1 \times 1.6 \times 10^{-19}}{1.38 \times 10^{-23}} \left(\frac{1}{T} - \frac{1}{300} \right) \right] \\ &= 8.625 \times 10^{-5} \times T \times \left(47.8 - 3 \ln T + 1.275 \times 10^4 \times \left(\frac{1}{T} - \frac{1}{300} \right) \right) (\text{volts}) \end{aligned}$$

Plot:



2. Refer to problem 1, the silicon bar has a cross section with diameter 20 μm . Assume that the depletion approximation holds. (a) Calculate W, X_{no} and X_{po} at 300 K. (b) Determine the total positive ion charge in the depletion region. (c) Sketch to scale the charge density $\rho(x)$, electrical field $\mathbf{E}(x)$, and electrostatic potential $V(x)$ in the depletion region. Assume that the electrostatic potential is zero at $x=0$. (d) Draw the energy band diagram for the device.

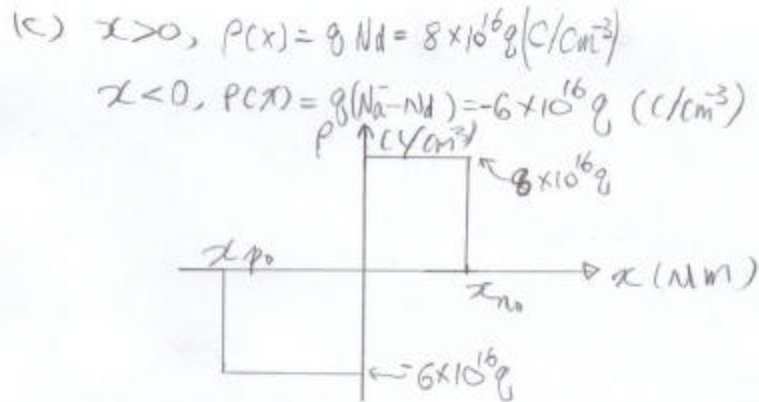
$$(a): W = \left[\frac{2eV_0}{q} \left(\frac{1}{N_a} + \frac{1}{N_d} \right) \right]^{1/2} = \left[\frac{2(11.8 \times 8.85 \times 10^{-14})(0.795)}{1.6 \times 10^{-19}} \left(\frac{1}{6 \times 10^{16}} + \frac{1}{8 \times 10^{16}} \right) \right]^{1/2} = 0.174 \text{ mm}$$

$$x_{n0} = \frac{W}{1 + N_d / N_a} = 0.0746 \text{ mm}$$

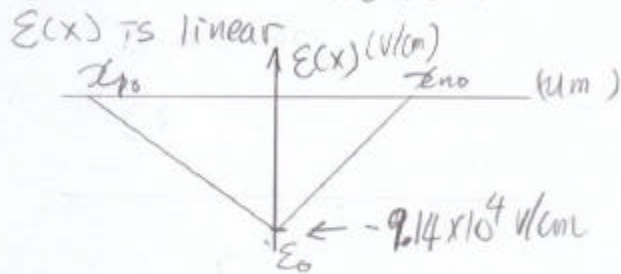
$$x_{p0} = \frac{W}{1 + N_a / N_d} = 0.0994 \text{ mm}$$

(b): $Q_+ = q A x_{n0} N_d = (1.6 \times 10^{-19}) [p \times (10 \times 10^{-4})^2] (7.46 \times 10^{-6}) (8 \times 10^{16}) = 3.00 \times 10^{-13} \text{ C}$

(c):



$$\mathcal{E}_0 = -\frac{q}{\epsilon} N_d x_{n0} = -\frac{1.6 \times 10^{19}}{11.8 \times 8.85 \times 10^{-14}} \times 8 \times 10^{16} \times 0.0746 \times 10^{-4} = -9.14 \times 10^4 \text{ V/cm}$$



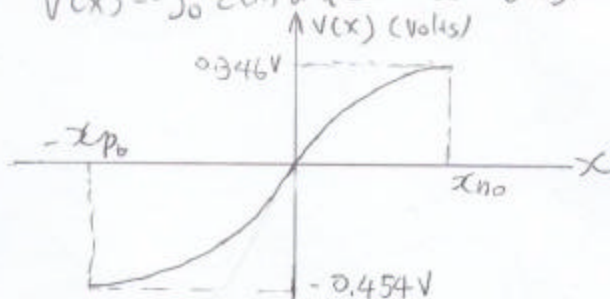
When $x < 0$,

$$V(x) = -\int_0^x \mathcal{E}(x) dx = -\int_0^x \frac{x+x_p}{x_{p0}} \mathcal{E}_0 dx = \int_0^x \frac{x}{x_{p0}} \mathcal{E}_0 dx - \mathcal{E}_0 x$$

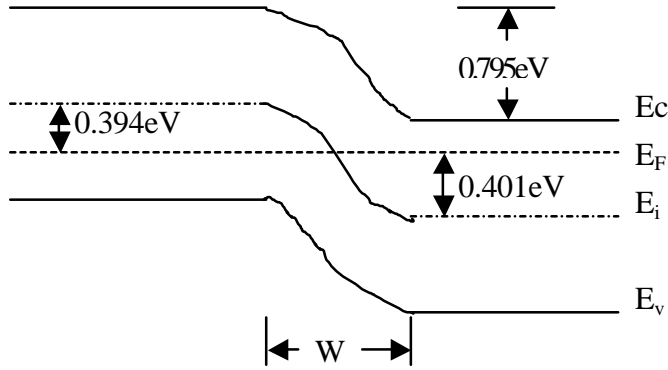
$$= -\frac{\mathcal{E}_0}{2x_{p0}} x^2 - x \mathcal{E}_0 = 4.6 \times 10^9 x^2 + 9.14 \times 10^4 x \quad (x \text{ in cm})$$

When $x > 0$

$$V(x) = -\int_0^x \mathcal{E}(x) dx = \dots = -6.13 \times 10^9 x^2 + 9.14 \times 10^4 x$$



(d):



3. Refer to problem 1 again. In reality, the alloying process will introduce a much higher concentration of acceptor. Assume that the uniform counter doping is $N_a = 3 \times 10^{19}/\text{cm}^3$ instead. Determine and plot the contact potential V_0 and depletion widths W , X_{n0} and X_{p0} versus temperature ranging from 250 K to 500 K.

$$V_0 = \frac{kT}{q} \ln \frac{N_a N_d}{n_i^2}, \quad |E_0| = \frac{qN_d x_{n0}}{e} = \sqrt{\frac{2qV_0}{e} \left(\frac{N_a N_d}{N_a + N_d} \right)}, \quad W = \sqrt{\frac{2eV_0}{q} \left(\frac{1}{N_a} + \frac{1}{N_d} \right)},$$

$$x_{n0} = \frac{W}{1 + N_d / N_a}, \quad x_{p0} = \frac{W}{1 + N_a / N_d}$$

Notice that n_i is a function of temperature. You can either use equation 3-26 or figure 3-17

Both are ok. If you use figure 3-17, at least 5 points need to be correctly read. Below I use eqn 3-26.

$$V_0 = \frac{kT}{q} \left[\ln \frac{N_a N_d}{n_i^2(300\text{K})} - 3(\ln T - \ln 300) + \frac{E_g}{k} \left(\frac{1}{T} - \frac{1}{300} \right) \right]$$

Using a computer program can greatly speed up calculation.

